

Heubach formulation No. 132-01

12/92

FUNCTION	PRODUCT	PRODUCER	PBW
Component A			
Epoxy	Beckopox EP 301/75X	Hoechst, today Cytec	23.90
Aromatic hydrocarbon	Xylene		8.59
Glycol ether	Solvenon PM	BASF	6.20
Solvent	Methyl isoamyl ketone		1.50
Antisettling agent	Anti-Terra-204	Byk-Chemie	0.50
Premix.			
Aromatic hydrocarbon	Xylene		4.60
Rheology modifier	Bentone 38	Rheox, today Elementis	0.25
Rheology modifier	Thixogel VP	Süd-Chemie	0.25
Mix until uniform paste prior to addition.			
Antisettling agent	Aerosil R 972	Degussa, today Evonik	0.40
Magnesium silicate	Finntalc M15	Finnminerals, today Mondo Minerals	14.30
Barium sulphate	Albaryt	Sachtleben	15.00
Titanium dioxide	Finntitan RR 2, today Kemira 650	Kemira	3.10
Anticorrosive pigment	HEUCOPHOS® ZPA	Heubach	7.40
Carbon black	Flammruß 101	Degussa, today Evonik	0.01
Grind with a bead mill.			
			86.00
Component B			
Curing agent	Versamid 115, 100%	Schering, today Cognis	8.40
Aromatic hydrocarbon	Xylene		5.60
Mix.			
			14.00
Mix components A and B at least 30 minutes prior to use.			

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			100.00
SPECIFICATIONS			
PVC in %			34.0
PVC / CPVC			0.6
Solids in %			62.9
Vol.-% Anticorrosive pigment reg. pigment/filler			22.0

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